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Advances in X-Ray/EUV Optics and Components XI

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Introduction

This volume contains papers presented at the conference on "Advances in X-ray/EUV Optics and Components XI", held in San Diego, California (United States), 28–29 August 2016, as part of the 2016 SPIE International Symposium on Optics + Photonics.

The conference consisted of a poster session and six oral sessions devoted to these topics: Sources and Beamlines, Soft X-ray Monochromators, Crystal Optics, X-ray Monochromators, Mirror and Multilayer Optics, and Refractive Lenses.

A total of 28 papers were presented; those that were submitted in time were published in this volume and the SPIE Digital Library also contains any late submissions.

The presentations at this conference covered the recent progress in a broad range of topics in X-ray / EUV optics and most notably in the area of X-ray lenses development which has seen significant advancements. Topics related to laboratory-based X-ray optics (and sources), X-ray metrology, and adaptive X-ray optics were not discussed at this conference, but were covered in three separate conferences at the same symposium.

This conference was augmented by the annual Workshop on X-ray Optics held on 30 August 2016, organized by Ali Khounsary and Daniele Cocco, which provides an informal forum to discuss topics in X-ray optics. This year's discussions covered challenges in advanced metrology for X-ray mirrors.

The conference chairs would like to thank the authors, speakers, session chairs, program committee members, and the conference participants for their contributions, and the SPIE staff for their exemplary assistance in the organization of the conference.

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